

# ABSTRACT

Novel silicon-containing polymers are obtained by  
5 copolymerizing a vinylsilane monomer with a compound having  
a low electron density unsaturated bond such as maleic  
anhydride, maleimide derivatives or tetrafluoroethylene.  
Using the polymers, chemical amplification positive resist  
compositions sensitive to high-energy radiation and having a  
10 high sensitivity and resolution at a wavelength of less than  
300 nm and improved resistance to oxygen plasma etching are  
obtained.

10085935, 030102